CLAIMS

1. A substrate processing device, comprising:

a first chamber in which a substrate support to receive a substrate is located;

a second chamber located in the first chamber, the second chamber defining, together with the substrate support, a processing space for processing the substrate received on the substrate support;

a clamp releasably fastening the second chamber to the first chamber; and

a releaser configured to release the second chamber fastened with the clamp,

wherein the second chamber includes

a wall including a peripheral wall surrounding the substrate support,

a circulation space defined at least in the peripheral wall to allow a gas to circulate in a direction in which the peripheral wall extends,

at least one supply port connecting with the circulation space to supply the gas, and

at least one outlet connecting with the circulation space to discharge the gas to at least one of an inside or an outside of the second chamber.

2. The substrate processing device according to claim 1, wherein

the wall of the second chamber further includes a ceiling continuous with the peripheral wall and facing the substrate support,

the circulation space is divided into a first circulation space extending in the ceiling in a

direction in which the ceiling extends and a second circulation space extending in the peripheral wall in a direction in which the peripheral wall extends, and

the at least one supply port includes a first supply port connecting with the first circulation space and a second supply port connecting with the second circulation space.

3. The substrate processing device according to claim 2, wherein

the first supply port and the second supply port are supplied with different gases.

4. The substrate processing device according to claim 1, wherein

the at least one outlet includes a first outlet being open to the inside of the second chamber and a second outlet being open to the outside of the second chamber.

5. The substrate processing device according to claim 1, wherein

the peripheral wall has air vents separated from the circulation space by partitions and connecting the inside and the outside of the second chamber,

the air vents are arranged in a staggered manner, and

the at least one outlet is located between adjacent air vents of the air vents and faces the inside of the second chamber.

6. The substrate processing device according to claim 1, further comprising:

a movable unit configured to vertically move the second chamber in the first chamber;

a lifter configured to move the movable unit vertically; and

a bellows connected to the movable unit and separating a space in the first chamber from

an outside of the first chamber,

wherein the second chamber is releasably fastened to the movable unit with the clamp, and

the gas is supplied to the at least one supply port through inside a space defined by the bellows.

7. The substrate processing device according to claim 1, wherein

the wall of the second chamber further includes a ceiling continuous with the peripheral wall and facing the substrate support.

8. The substrate processing device according to claim 1, further comprising:

a movable unit configured to vertically move the second chamber in the first chamber; and

a lifter configured to move the movable unit vertically,

wherein the second chamber is releasably fastened to the movable unit with the clamp.

9. An inner chamber assembly installable in a chamber in a substrate processing device, the inner chamber assembly comprising:

a wall including a peripheral wall surrounding a substrate support to receive a substrate;

a connector connected to a clamp releasably fastening the wall to the chamber;

a circulation space defined at least in the peripheral wall to allow a gas to circulate in a direction in which the peripheral wall extends;

at least one supply port connecting with the circulation space to supply the gas; and

at least one outlet connecting with the circulation space to discharge the gas to at least one

of an inside or an outside of the wall.

10. The inner chamber assembly according to claim 9, wherein

the wall further includes a ceiling continuous with the peripheral wall and facing the substrate support.

11. The inner chamber assembly according to claim 9, wherein

the at least one outlet includes a first outlet being open to an inside of the peripheral wall and a second outlet being open to an outside of the peripheral wall.

12. The inner chamber assembly according to claim 9, wherein

the peripheral wall has air vents separated from the circulation space by partitions and connecting an inside and an outside of the peripheral wall,

the air vents are arranged in a staggered manner, and

the at least one outlet is located between adjacent air vents of the air vents and faces the inside of the peripheral wall.

13. The inner chamber assembly according to claim 10, wherein

the circulation space is divided into a first circulation space extending in the ceiling in a direction in which the ceiling extends and a second circulation space extending in the peripheral wall in a direction in which the peripheral wall extends, and

the at least one supply port includes a first supply port connecting with the first circulation space and a second supply port connecting with the second circulation space.